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U.S. PATENT DOCUMENTS

Examiner
initials
for this
application

EXAMINER INITIALS	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPR.
JPB	4,256,828	3/17/81	George H. Smith	430	280.1	
PRM	4,882,245	11/21/89	Jeffrey D. Gelorme, et al.	430	280.1	
JPB	4,940,651	7/10/90	Lawrence M. Brown, et al.	430	280.1	
MEM	5,026,624	6/25/91	Richard A. Day, et al.	430	280.1	
JJS	5,043,221	8/27/91	Joseph V. Koleske	428	413	
CH	5,098,616	3/24/92	Edward D. Babich, et al.	430	280.1	
MEM	5,102,772	4/7/92	Raymond W. Angelo, et al.	430	280.1	
MEM	5,278,010	1/11/94	Richard A. Day, et al.	430	280.1	
MEM	5,304,457	4/19/94	Richard A. Day, et al.	430	280.1	
SR	5,859,655	1/12/99	Jeffrey Donald Gelorme, et al.	204	501	

FOREIGN PATENT DOCUMENTS

EXAMINER INITIALS	DOCUMENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO

OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)

- Crivello et al. "Photoinitiated Cationic Polymerization with Triarylsulfonium Salts", Journal of Polymer Science: Polymer Chemistry Edition, Vol. 17, pp. 977-999 (1979).
- N. La Branca and J.D. Gelorme, "High Aspect Ratio Resist for Thick Film Applications", Proc. SPIE, Vol. 2438, pp. 846-852 (1995).
- K.Y. Lee et al., "Micromachining applications of a high resolution ultrathick photoresist", J. Vac. Sci. Technology B 13(6), Nov./Dec. 1995.
- Sotec Microsystems Photoepoxies Product Brochure

EXAMINER: *Cyrtina Hunter* DATE CONSIDERED: 02-9-03

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.